

US PATENT & TRADEMARK OFFICE

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3	20220064803 Hafnium Oxide Corrosion Inhibitor
4	20220044929 FUNCTIONALIZED CYCLOSILAZANES AS PRECURSORS FOR HIGH GROWTH RATE SILICON-CONTAINING FILMS
5	20220044928 SILICON COMPOUNDS AND METHODS FOR DEPOSITING FILMS USING SAME
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12	20210363639 COMPOSITION FOR HIGH TEMPERATURE ATOMIC LAYER DEPOSITION OF HIGH QUALITY SILICON OXIDE THIN FILMS
13	20210363162 Low Halide Lanthanum Precursors For Vapor Deposition
14	20210340673 TRISILYLAMINE DERIVATIVES AS PRECURSORS FOR HIGH GROWTH RATE SILICON-CONTAINING FILMS
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16	20210339280 SILACYCLIC COMPOUNDS AND METHODS FOR DEPOSITING SILICON-CONTAINING FILMS USING SAME
17	20210324270 Low Oxide Trench Dishing Chemical Mechanical Polishing
18	20210309885 Low Oxide Trench Dishing Chemical Mechanical Polishing
19	20210301405 Barrier Chemical Mechanical Planarization Slurries For Cobalt Films

